

Title (en)
GAS DISTRIBUTION SYSTEM

Title (de)
GASVERTEILUNGSVORRICHTUNG

Title (fr)
UNITE DE REPARTITION DE GAZ

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Abstract (en)
[origin: WO9965057A1] The present invention generally provides a substrate processing chamber (14) having a gas distributor (54) that provides a uniform distribution of a gas concentration within the chamber. More particularly, the present invention provides an apparatus for distributing a process gas within a processing chamber that provides a uniform distribution of gas concentration within the processing chamber. Another aspect of the present invention provides for such an apparatus for gas distribution that can be used in CVD, PVD and etching chambers. The present invention generally provides an apparatus for distributing gas within a substrate processing chamber comprising a gas distributor (54) made of gas permeable material having a conduit (50) disposed within the gas distributor.

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